

Predicting A Novel Phase of 2D SiTe₂

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ABSTRACT

Layered IV-VI₂ compounds often exist in the CdI₂ structure. Using the evolution algorithm and first-principles calculations, we predict a novel layered structure of silicon ditelluride (SiTe₂) that is more stable than the CdI₂ phase. The structure has a triclinic unit cell in its bulk form and exhibits the competition between the Si atoms' tendency to form tetrahedral bonds and the Te atoms' tendency to form hexagonal close-packing. The electronic and vibrational properties of the predicted phase are investigated. The effective mass of electron is small among 2D semiconductors, which is beneficial for applications such as field-effect transistors. The vibrational Raman and IR spectra are calculated to facilitate future experimental investigations.

I. INTRODUCTION

The investigation and characterization of two dimensional (2D) materials have been increased significantly since the last decade. Synthesis of many novel 2D materials including graphene^{1,2}, hexagonal boron nitrides^{3,4}, transition metal dichalcogenides^{5,6}, phosphorene^{7,8}, and silicene^{9,10} drives rapid progress in the field. These materials attract significant interest because of their intriguing properties different than in their bulk forms due to the reduced dimension, such as quantum confinement, mechanical flexibility, lack of dielectric screening, and large surface areas. These properties are beneficial for a wide range of potential applications in optoelectronics^{11,12}, chemical sensors¹³, photovoltaics¹⁴, energy storage¹⁵, nanoelectronics¹⁶, and many more.

The IV_x-VI_y compound family contains a number of materials with layered crystal structures from which 2D crystalline mono- and multi-layers can be obtained. The IV-VI group includes 2D

SnSe¹⁷, SnS, GeS, and GeSe¹⁸, which adopt a puckered layer structure with C_{2v} symmetry. The 2D IV-VI₂ materials include SnS₂¹⁹ and SnSe₂²⁰, whose bulk forms adopt the CdI₂-type crystal structures with P3m1 space group. The Si_x-Te_y system is a particularly interesting member of the IV_x-VI_y family, as Si is a small group 4 element, and Te is a large group 6 element. The silicon telluride (Si₂Te₃)^{21,22} is the most studied Si_x-Te_y compound^{23–29}. It is the only known IV₂-VI₃ material with a layered structure^{21,30} and features a unique structural variability because of the orientation of silicon dimers²⁴. The other Si_x-Te_y compound is silicon ditelluride (SiTe₂)^{31–34}, whose electrical, thermal, and magnetic properties have recently drawn a number of investigations^{35–37}. The crystal structure of SiTe₂ is identified by the CdI₂-type^{34,38} as other 2D IV-VI₂ materials, although it was suggested that it may also exist in the Si₂Te₃ structure with Si deficiency³⁹.

In this paper, we use results from the evolutionary algorithm and first-principles calculations to predict a new layered crystal structure of SiTe₂ that is more stable than the CdI₂-type structure. The predicted bulk structure has a triclinic unit cell. The atomic structure indicates the competition between the Si atoms' tendency to form tetrahedral bonds and the Te atoms' tendency to form hexagonal close-packing. The material has a low electron effective mass and anisotropic hole effective mass that can be beneficial for potential applications. The Raman and IR spectra are calculated, which can be useful for future experimental investigations.

II. COMPUTATIONAL METHODS

Evolutionary Algorithm. The global search of stable crystal structures of bulk SiTe₂ was done using the evolutionary algorithm as implemented in the universal crystal structure predictor USPEX^{40,41}. The initial population (first generation) consists of 30 structures generated randomly by using the space group symmetry under fixed chemical composition Si:Te=1:2. The number of structures in each generation is kept constant. The genetic evolutionary could stop if the best structure did not change for ten generations. We use 60% of the current generation to produce the next generation. In total, 50% of the generation was produced by heredity, 30% of generation produced randomly from space groups, and 20% of the generation produced by soft mutations in each generation afterward. The external pressure is set to zero. The structural relaxations and total energy calculations are carried using density functional theory (DFT) as implemented in the VASP

(Vienna Ab initio Simulation Package) code⁴². The pseudopotentials are constructed under the projected augmented wave (PAW) method⁴³. We used the Perdew-Burke-Ernzerhof (PBE) form of exchange-correlation functional⁴⁴ under generalized gradient approximation (GGA). The global break conditions for the electronic and ionic steps are 10^{-5} eV and 10^{-4} eV/Å, respectively. During the evolutionary search of structures, the maximum kinetic energy cutoff for the plane-wave basis is 320 eV.

Density Functional Theory Calculations. After we found the most stable structure of bulk SiTe₂, we construct the monolayer and investigate the electronic properties of both bulk and the monolayer through DFT and hybrid DFT calculations. These calculations are carried out using the VASP code and the same pseudopotentials as in the evolutionary algorithm search. We use the PBE functional for DFT calculations and hybrid HSE06 functional^{45,46} for hybrid DFT calculations. The convergence conditions for the electronic and ionic steps are 10^{-9} eV and 10^{-8} eV, respectively. The kinetic energy cutoff for the plane-wave basis set was 500 eV. Brillouin zones for bulk and monolayer SiTe₂ respectively were sampled at $13 \times 13 \times 7$ and $13 \times 13 \times 1$ k-point grids centered at the Γ point. The spin-orbit coupling effects are considered for the band structure calculations. For the model of the monolayer structure, a vacuum of 13.7 Å is inserted between the periodic replicas of the monolayer to avoid artificial interactions. To confirm the dynamical stability, we performed the phonon calculations of a $5 \times 5 \times 1$ supercell of the monolayer using the finite displacement method as implemented in the Phonopy program⁴⁷. To further verify the dynamical stability, we carried out ab-initio molecular dynamic simulations (AIMD) in a $4 \times 4 \times 1$ supercell of the monolayer at 500 K. The time step was set to 2 fs with a total simulation time of 20 ps.

Raman and IR spectra. We carried out density functional perturbation theory (DFPT)⁴⁸ calculations as implemented in Quantum Espresso package⁴⁹ to obtain the Raman and IR spectra of bulk and monolayer of SiTe₂. The calculations use the Perdew-Zunger functional⁵⁰ under the local density approximation and the norm-conserving pseudopotential⁵¹. Reciprocal space was sampled with a k-point grid of $13 \times 13 \times 7$ for bulk and $13 \times 13 \times 1$ for monolayer centered at the Γ point. The cutoff energy of the plane-wave basis is 80 Ry. The Raman and IR spectra calculations start from the charge densities that are converged to 10^{-14} Ry in total energy.

III. RESULTS AND DISCUSSION

Structures. A total of 382 stable crystalline structures are generated by the evolution algorithm. In Figure 1a we plotted the energy per atom of each of the generated structures. We obtain the lowest energy structure with the total energy of -3.88 eV/atom. The top and side views of the corresponding structure are shown in Figures 2a and 2b. The structure features a triclinic crystal lattice with a space group P1. The primitive unit cell consists of three atoms (one Si atom and two Te atoms). The lattice parameters of this lowest energy of SiTe₂ are shown in Table I. The evolutionary algorithm search also found the CdI₂-type structure of SiTe₂ that was previously reported^{34,38} with the total energy of -3.81 eV/atom. Thus the new predicted structure is energetically more stable than the common CdI₂-type structure that has been reported in SiTe₂.

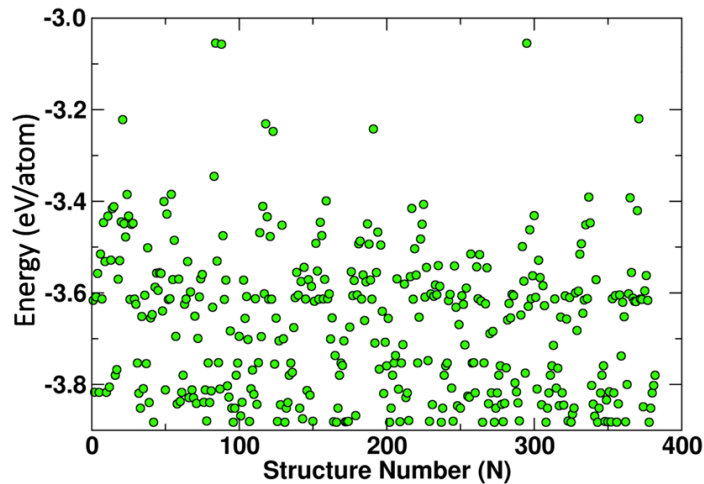


Figure 1: Energies for all the generated structures of SiTe₂.

It is interesting to discuss why this structure exists in SiTe₂ and is more stable than the CdI₂-type structure. In Figure 2c, we show the local bonding structure of Si in this new structure. The Si atom is clearly tetrahedrally bonded, which indicates covalent bonding from sp³ hybridization of Si 3s and 3p orbitals. Meanwhile, in the CdI₂-type structure, the cations are six-coordinated (Figure 2d). Given the strong tendency of Si to form such covalent bonds, it is reasonable to state that forming six-coordinated Si is associated with an energy penalty compared with four-coordinated Si. On the other hand, the tetrahedral around the Si atoms are strongly distorted. As

shown in Table II, there is a large variety of the Te-Te distances in the tetrahedral surrounding the Si atom, ranging from 3.945 Å to 4.516 Å. The reason for this distortion is that due to its large size, the Te atom prefers hexagonal close-packed (HCP) structure, which is not fully compatible with the tetrahedral bonding of Si. The competing requirements lead to the distorted bonding around Si atoms along with a slightly distorted HCP packing of Te, as can be seen in Figures 2e and 2f.

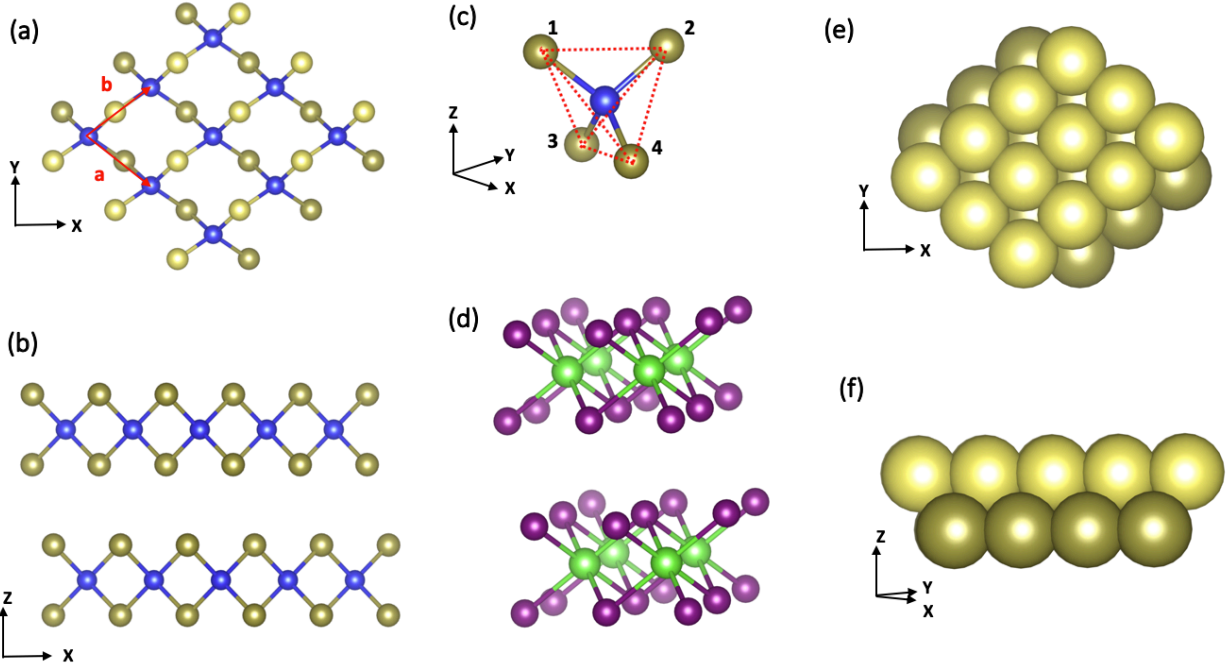


Figure 2: (a) Top and (b) side views of the crystal structure of SiTe₂ with unit lattice vector marked by solid red lines. Te and Si atoms are represented by tan and blue colors, respectively. The Te atoms in the upper layer are shown in the brighter tan color. (c) The bonding configuration near a Si atom. (d) The CdI₂ structure. (e) Top and (f) side views of the space-filling plot showing the packing of Te atoms.

Table I: Structural parameters of predicted bulk and monolayer SiTe₂.

	<i>a</i> (Å)	<i>b</i> (Å)	<i>c</i> (Å)	α (°)	β (°)	γ (°)	<i>d</i> _{Si-Te} (Å)
Bulk	3.945	3.945	7.076	83.68	83.77	75.98	2.561
Monolayer	3.941	3.941	N/A	N/A	N/A	75.88	2.558

Table II: Nearest neighbor Te-Te distances in bulk SiTe₂.

$d_{\text{Te1-Te2}} (\text{\AA})$	$d_{\text{Te1-Te3}} (\text{\AA})$	$d_{\text{Te1-Te4}} (\text{\AA})$	$d_{\text{Te2-Te3}} (\text{\AA})$	$d_{\text{Te2-Te4}} (\text{\AA})$	$d_{\text{Te3-Te4}} (\text{\AA})$
3.945	4.070	4.516	4.502	4.070	3.945

Dynamical Stability. In order to determine whether the predicted structure is dynamical stable, we calculated the phonon dispersion of the monolayer SiTe₂ along the high symmetry lines of Brillouin zones using the finite displacement method. The phonon spectrum (Figure 3a) shows no significant negative frequencies, therefore indicating the structure is dynamically stable. The very small negative frequencies in the acoustic mode near the Γ point are numerical artifacts due to the use of a finite FFT grid. The dynamical stability is further examined by the ab-initio molecular dynamic (AIMD) simulation at 500 K. As shown in Figure 3b, the total energy fluctuates during the simulation without any sudden drop of the energy that would indicate a phase transition. The snapshot confirms that the structure remains stable during the AIMD simulations.

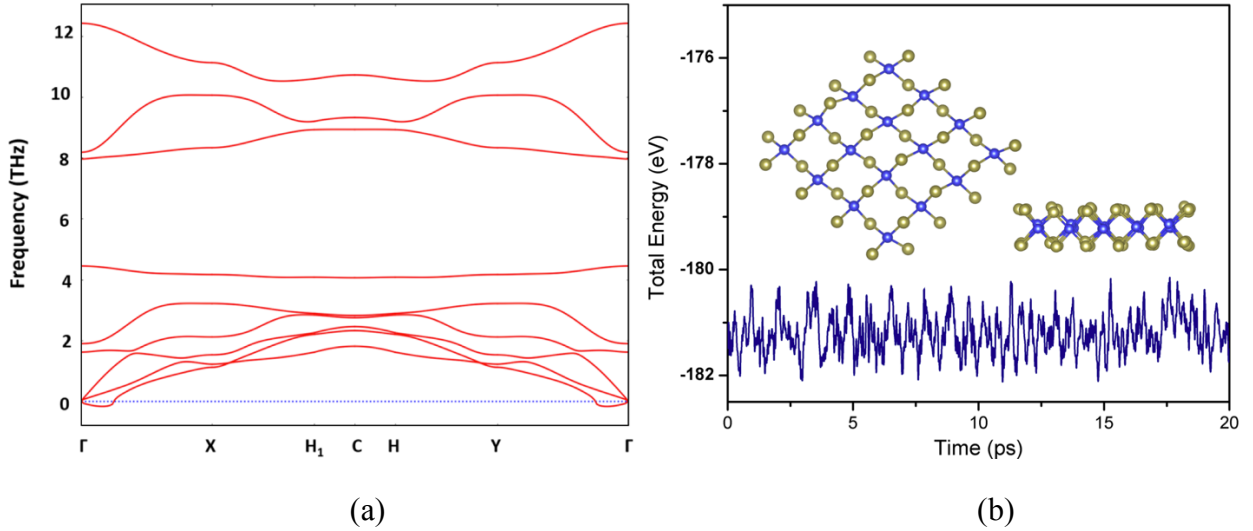


Figure 3: (a) Phonon band structures of the monolayer of SiTe₂. (b) A snapshot of for AIMD simulation at 500 K and the variation of total energy in AIMD simulation during a timescale of 20 ps.

Electronic Structure. To understand the electronic properties of SiTe₂, we studied the band structures of both the bulk and monolayer along the high symmetry lines of Brillouin zones using

the DFT method. Figures 4(a) and 4(b) represent the electronic band structures of bulk and monolayer SiTe_2 , taking into account the spin-orbit interaction. The bandgap is 0.206 eV for bulk and 0.552 eV for the monolayer. In bulk SiTe_2 , the valence band maximum (VBM) lies between the Γ and Z and the conduction band minimum (CBM) is at Γ . Meanwhile, both VBM and CBM are located at the Γ point in the monolayer. These results indicate that the bulk and monolayer SiTe_2 are indirect and direct bandgap semiconductors, respectively. The bandgap in the monolayer is higher than in bulk because of the quantum confinement effect. Since DFT is known to underestimate the bandgap, we used the hybrid DFT method with the HSE06 functional. Figure 5 below represents the band structures of SiTe_2 under the HSE06 approach. The band structures are similar to the DFT band, except that the band gaps for bulk and monolayer have increased to 0.831 and 1.222 eV, respectively.

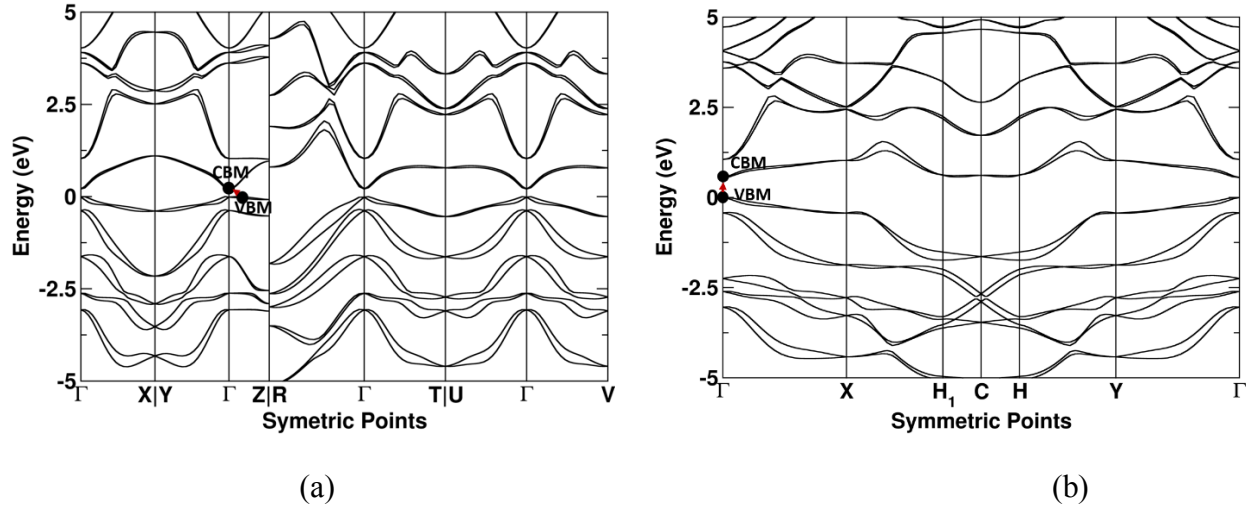


Figure 4: Electronic band structures of (a) bulk and (b) monolayer SiTe_2 under DFT approach showing the indirect and direct band gaps taking the spin-orbit interaction into account.

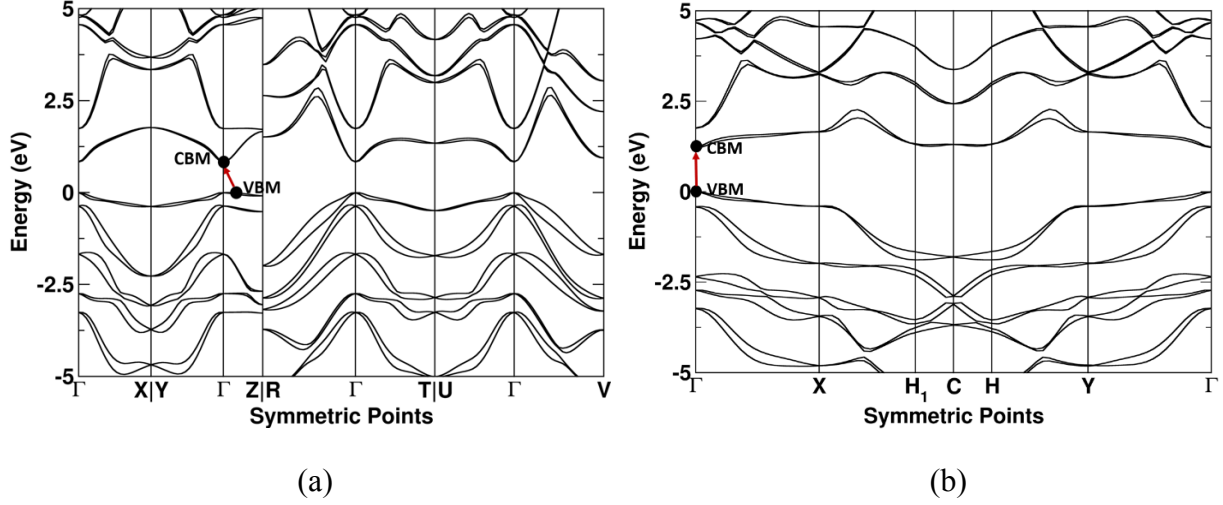


Figure 5: Electronic band structures of (a) bulk and (b) monolayer SiTe₂ with HSE06 functional.

The effective masses of the electrons and holes in SiTe₂ are obtained by fitting the DFT bands near the CBM and VBM using the relationship $m^* = \hbar^2 / (\frac{\partial^2 E}{\partial k^2})$. The results are shown in Table III. The electron effective mass bulk is $0.116 m_0$ in the x-direction, which is comparable to black phosphorous ($m^* = 0.12 m_0$)⁵² and four times smaller than MoS₂ ($m^* = 0.45 m_e$)⁵³. The low electron effective mass suggests high electron mobility, which is beneficial for applications such as field-effect transistors. An in-plane anisotropy is observed for the holes, where the effective mass along the y-direction is 3 to 4 times the value along the x-direction. Such anisotropy may be beneficial for designing devices such as angle-dependent optoelectronic applications⁵⁴.

Table III: The carrier effective masses in SiTe₂.

	carrier	xx (m_0)	yy (m_0)	zz (m_0)
Bulk	e	0.116	0.163	0.229
	h	0.160	0.667	4.329
Monolayer	e	0.177	0.227	N/A
	h	0.262	0.623	N/A

Figure 6a shows the partial and total densities of states (DOS) of bulk SiTe₂ from HSE calculations. The conduction bands consist both the p orbitals of Si atoms and the p orbitals of Te atoms. Meanwhile, the valence bands are mainly due to the p orbitals of Te atoms. To better

understand the contribution of each atomic orbitals to the band structures, we analyze the wave functions at band edges. Figure 6b and 6c represent the square of the wave functions at CBM and VBM. It can clearly be seen the s orbitals of Si atoms along with p_x+p_y orbitals of Te atoms play a major role at CBM, while the VBM mainly consists of p_x+p_y orbitals of Te atom. It is interesting to note that the p_x+p_y orbitals from adjacent Te atoms tend to align with the Te-Te direction, which indicates the σ type bonding between Te atoms.

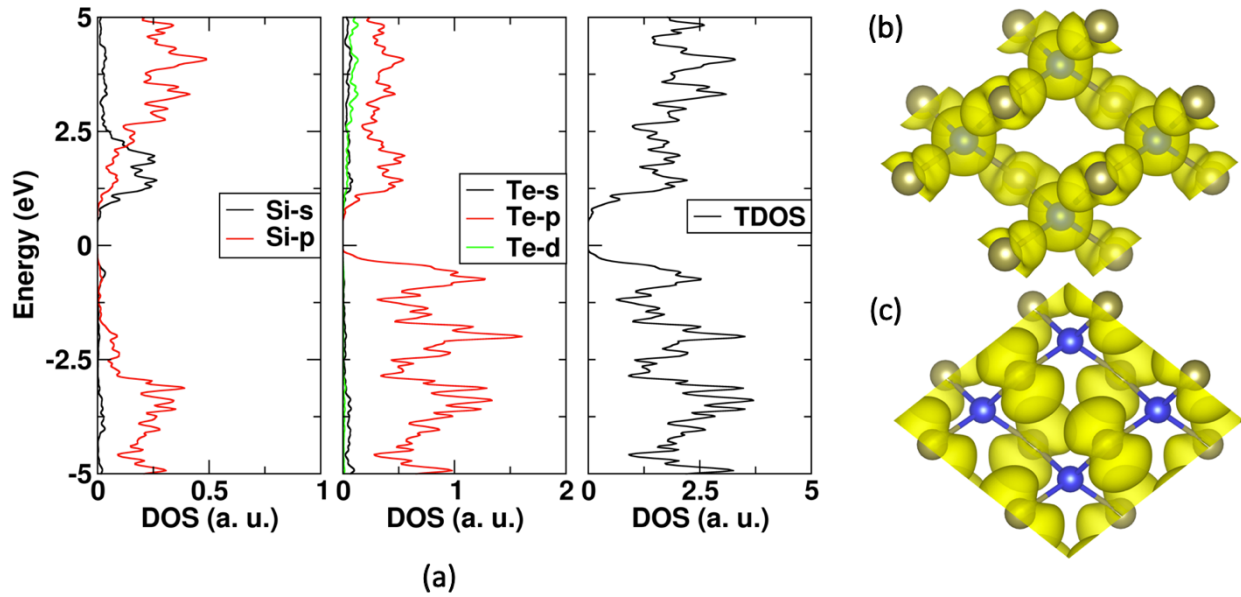


Figure 6: (a) Partial and total DOS of SiTe_2 from HSE calculations. Charge density plots at CBM (b) and VBM (c).

Raman and IR spectra. Vibrational spectroscopy is widely used to characterize 2D materials. To facilitate future experimental investigation of the predict phase of SiTe_2 , we present the calculated Raman spectra of bulk and monolayer SiTe_2 with the respective vibrational modes in Figure 7. We found the bulk SiTe_2 has three major Raman peaks at 144.06 cm^{-1} , 261.73 cm^{-1} , and 409.90 cm^{-1} , whereas the monolayer SiTe_2 has two major Raman peaks at 147.35 cm^{-1} and 413.88 cm^{-1} . The $144.06/147.35 \text{ cm}^{-1}$ peak corresponds to the out-of-plane vibration mode from the Te atoms, while the $409.90/413.88 \text{ cm}^{-1}$ peak corresponds to the out-of-plane vibration mode from the Si atoms. The peak at 261.73 cm^{-1} in bulk SiTe_2 corresponds to the in-plane vibration of Si atoms.

This mode has negligible Raman intensity in the monolayers while being significant in bulk, indicating the effect of interlayer coupling.

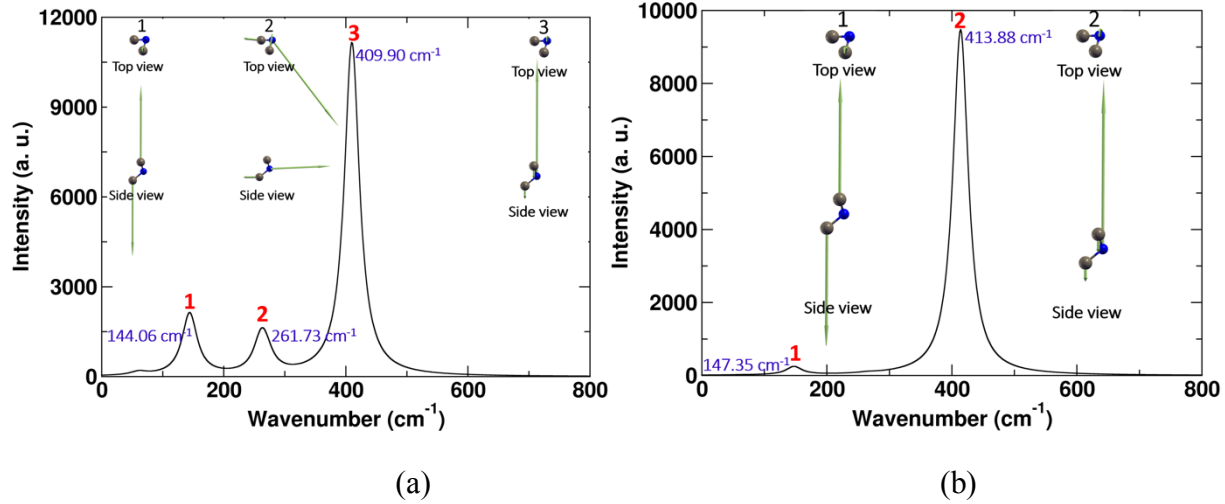


Figure 7: Raman spectra of (a) bulk and (b) monolayer SiTe₂ showing major peaks.

Figure 8 shows the calculated IR spectra. The bulk SiTe₂ has two major peaks at 269.89 cm⁻¹ and 409.00 cm⁻¹. The former corresponds to an in-plane vibration mode of Si atoms that is orthogonal to the Raman-active in-plane Si vibration mode at 261.73 cm⁻¹, while the latter is the same as the Raman-active out-of-plane Si vibration mode. The monolayer SiTe₂ has only one major Raman peaks at 271.79 cm⁻¹. The mode around 410 cm⁻¹ that is IR active in bulk is inactive in the monolayers, again indicating the effect of interlayer coupling. This feature may be useful for identifying the thickness of the SiTe₂ layers in experiments.

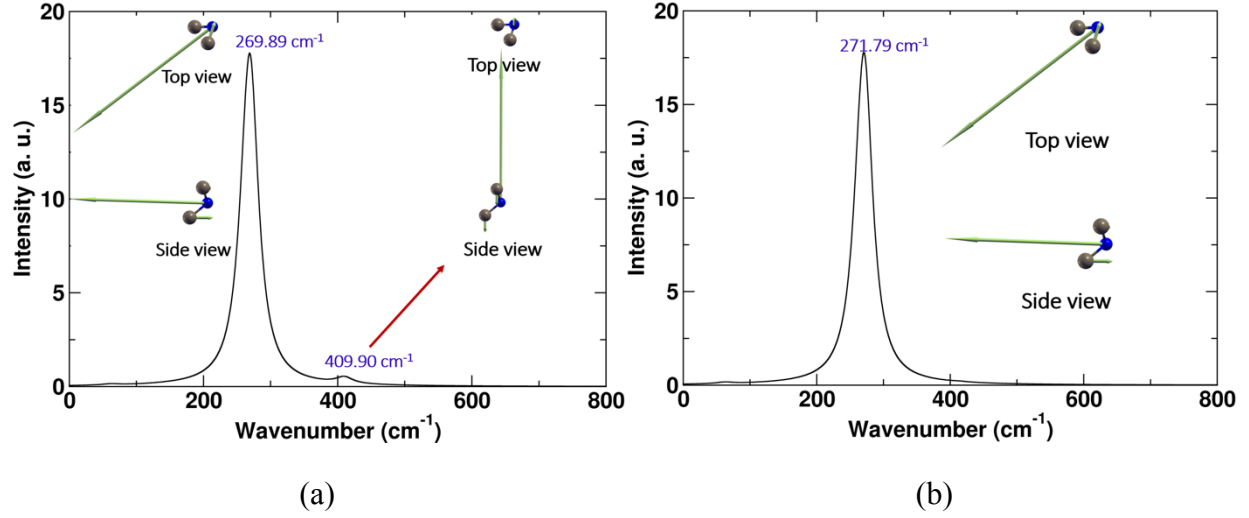


Figure 8: IR spectra of (a) bulk and (b) monolayer SiTe₂ showing major peaks.

IV. SUMMARY

In summary, we use the evolution algorithm coupled with the first-principles calculations to predict a novel 2D layered structure of silicon telluride (SiTe₂), which is different from the known layered CdI₂-type structure in IV-VI₂ materials. The structure features a distorted tetrahedral bonding for Si atoms and a distorted hexagonal close pack stacking of Te atoms, indicating that structure forms as a compromise of these two competing requirements. We confirm the dynamical stability of the structure using both phonon dispersion and the AIMD simulations. Electronic properties are investigated by both the DFT and hybrid DFT methods. The new SiTe₂ phase is a semiconductor with an indirect bandgap in its bulk form and a direct bandgap in its monolayer form. It features electron effective mass of 0.12 m_0 , which is low among 2D semiconductors. The Raman and IR spectra for the bulk and monolayers are also predicted.

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